

55:131

Introduction to VLSI Design



Flash and DRAM

Adapted from Weste and Harris notes except as noted

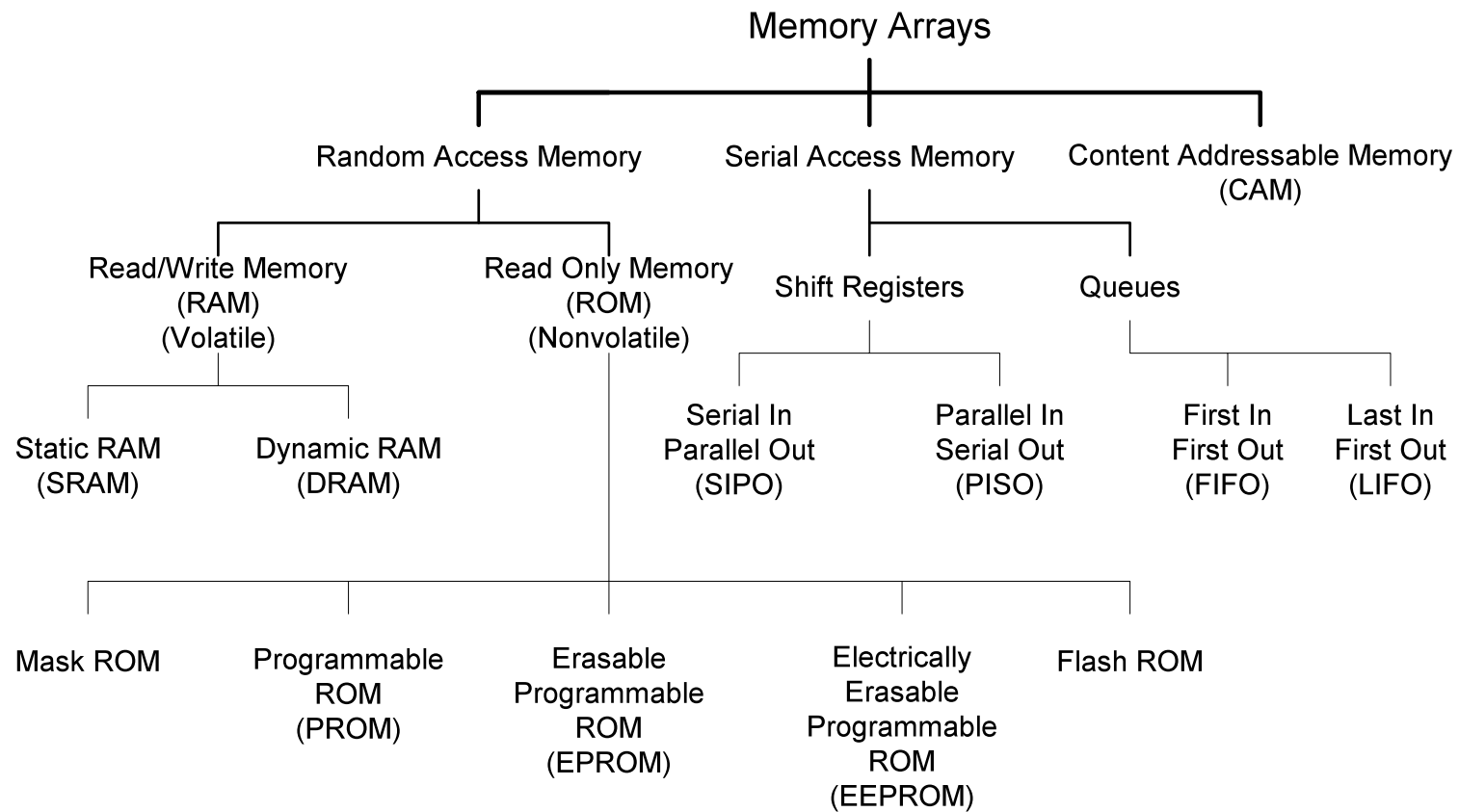
Flash and DRAM sections adapted from “Digital
Integrated Circuits”, copyright 2003 Prentice Hall/
Pearson



Outline

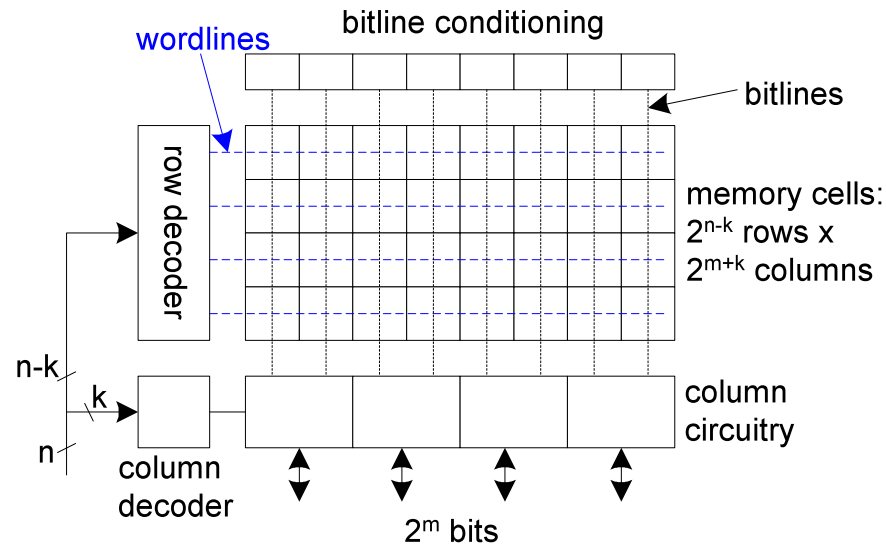
- Memory Arrays
- Flash
- DRAM

Memory Arrays



Array Architecture

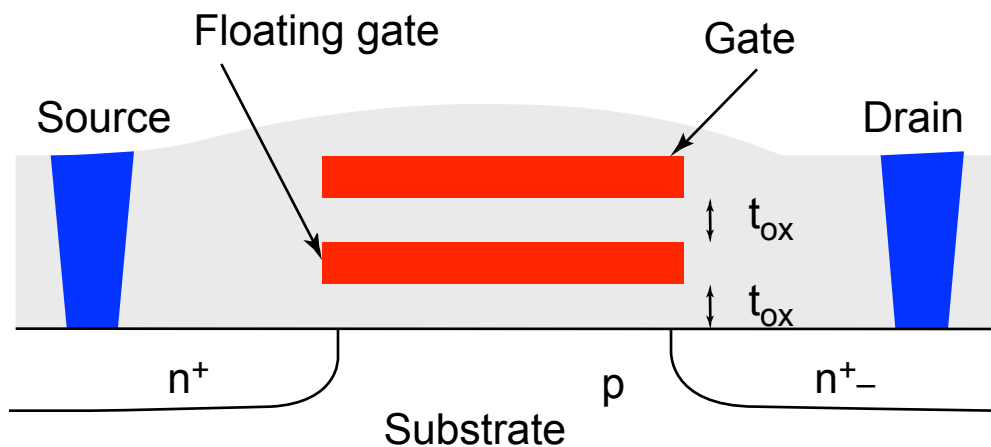
- 2^n words of 2^m bits each
- If $n \gg m$, fold by 2^k into fewer rows of more columns



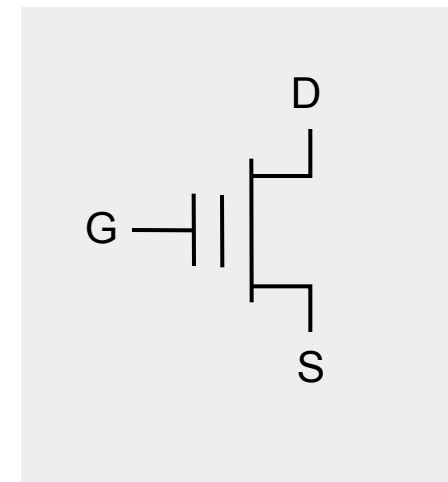
- Good regularity – easy to design
- Very high density if good cells are used

Non-Volatile Memories

□ Floating-gate transistor




Device cross-section




Schematic symbol


Floating-Gate Transistor Programming


0 V 20 V

 20 V 20 V
 Erase Inhibit Erase

FN Tunneling
 Remove e-
 Negative V_t
 "1"

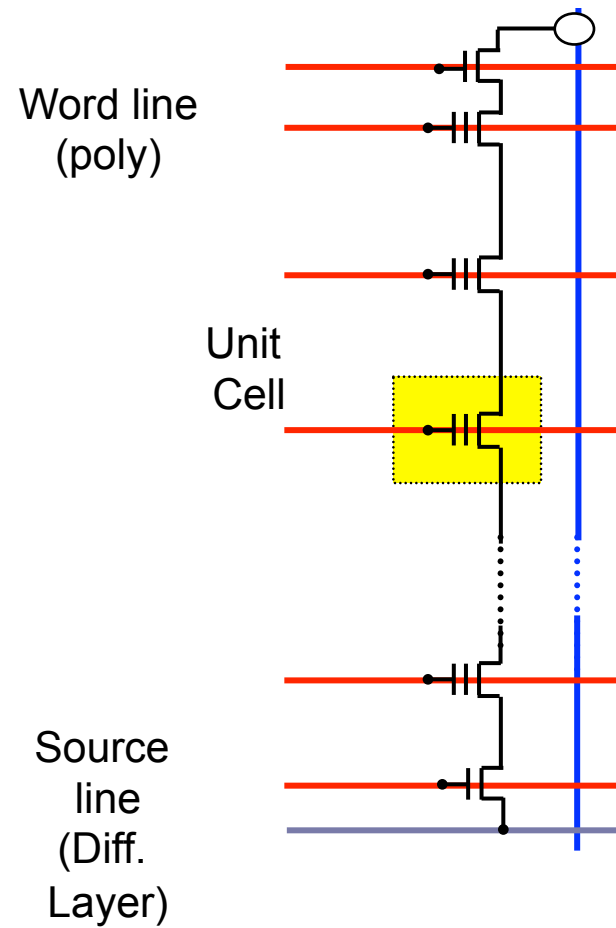
20 V
 0 V  0 V
 0 V
 Program 0

FN Tunneling
 Add e-
 Positive V_t
 "0"

20 V
 8 V  8 V
 0 V
 Do Not Program

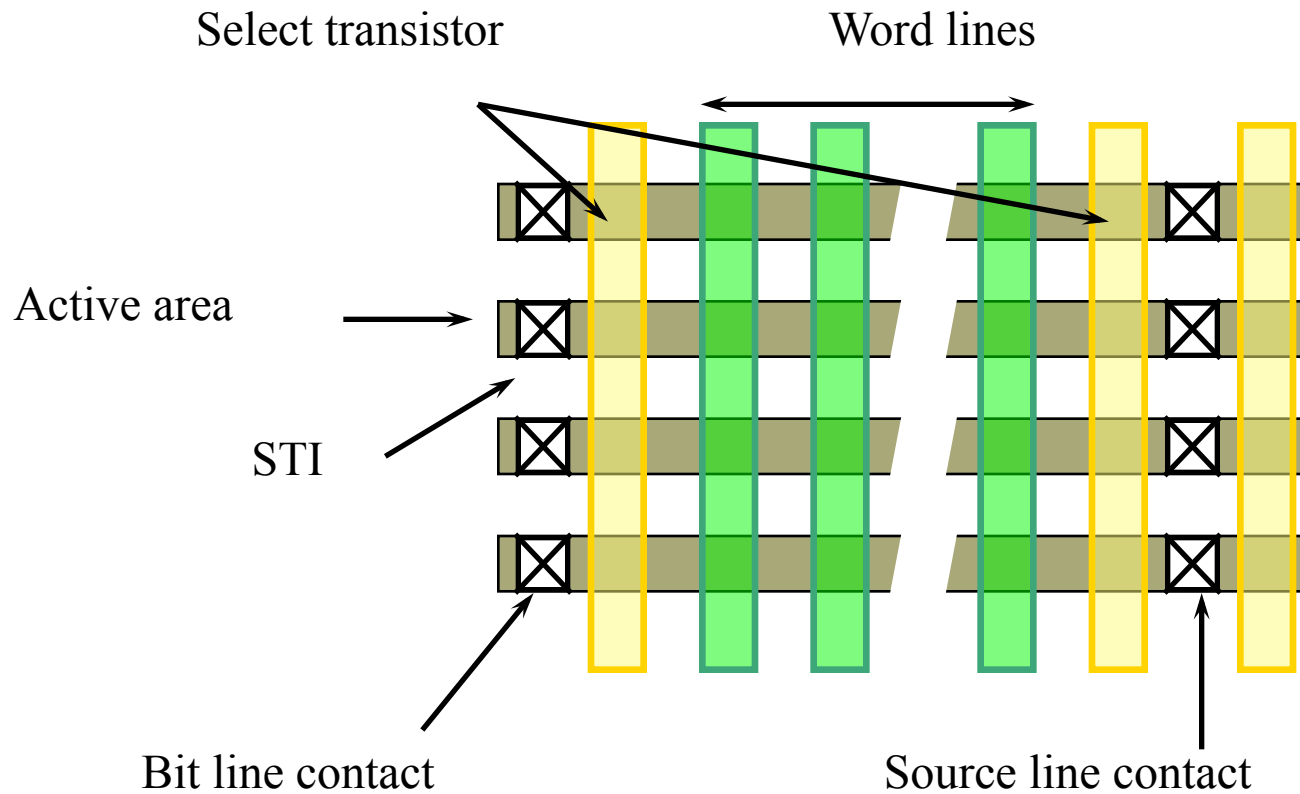
10 V
 $?$  $?$
 0 V
 Inhibit Program

NAND Flash Memory



Courtesy Toshiba

NAND Flash Memory



Read-Write Memories (RAM)

□ Static (SRAM)

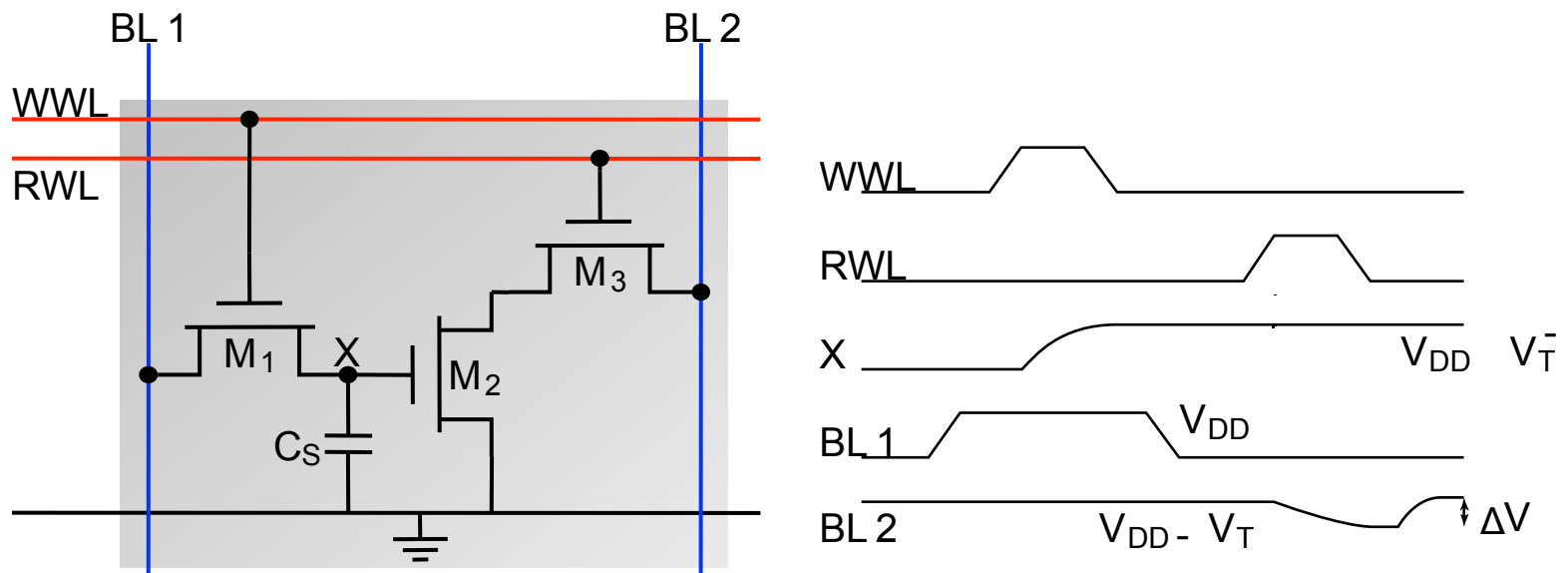
- Data stored as long as supply is applied
- Large (6 transistors/cell)
- Fast
- Differential

□ Dynamic (DRAM)

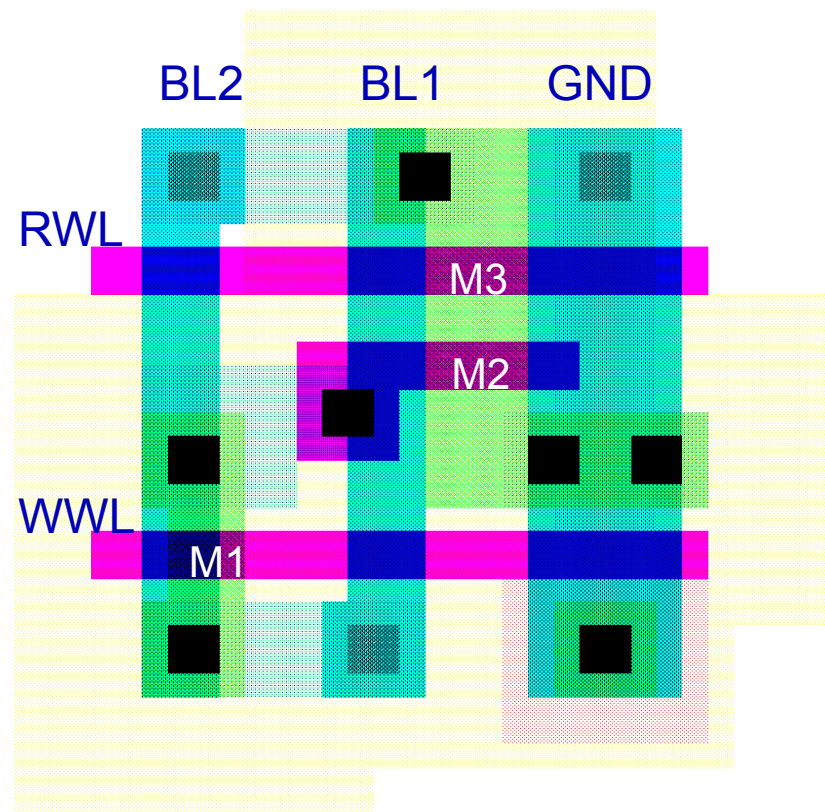
- Periodic refresh required
- Small (1-3 transistors/cell)
- Slower
- Single Ended

3-Transistor DRAM Cell

- No constraints on device ratios
- Reads are non-destructive
- Value stored at node X when writing a “1” = $V_{\text{wwl}} - V_{\text{tn}}$

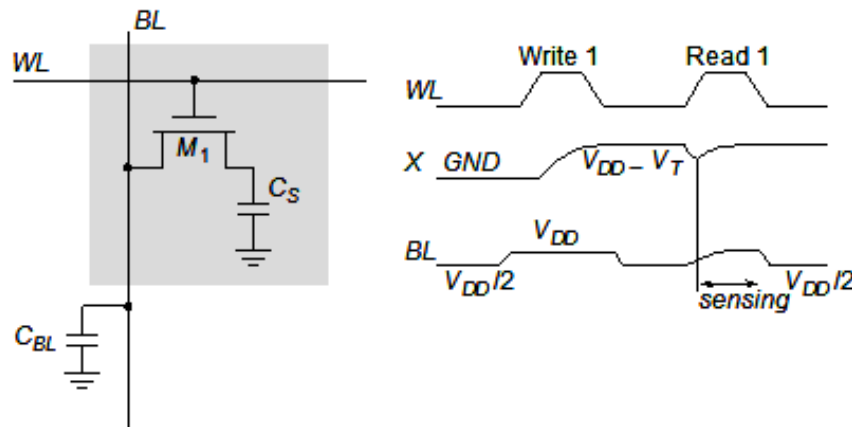


3T-DRAM — Layout



1-Transistor DRAM Cell

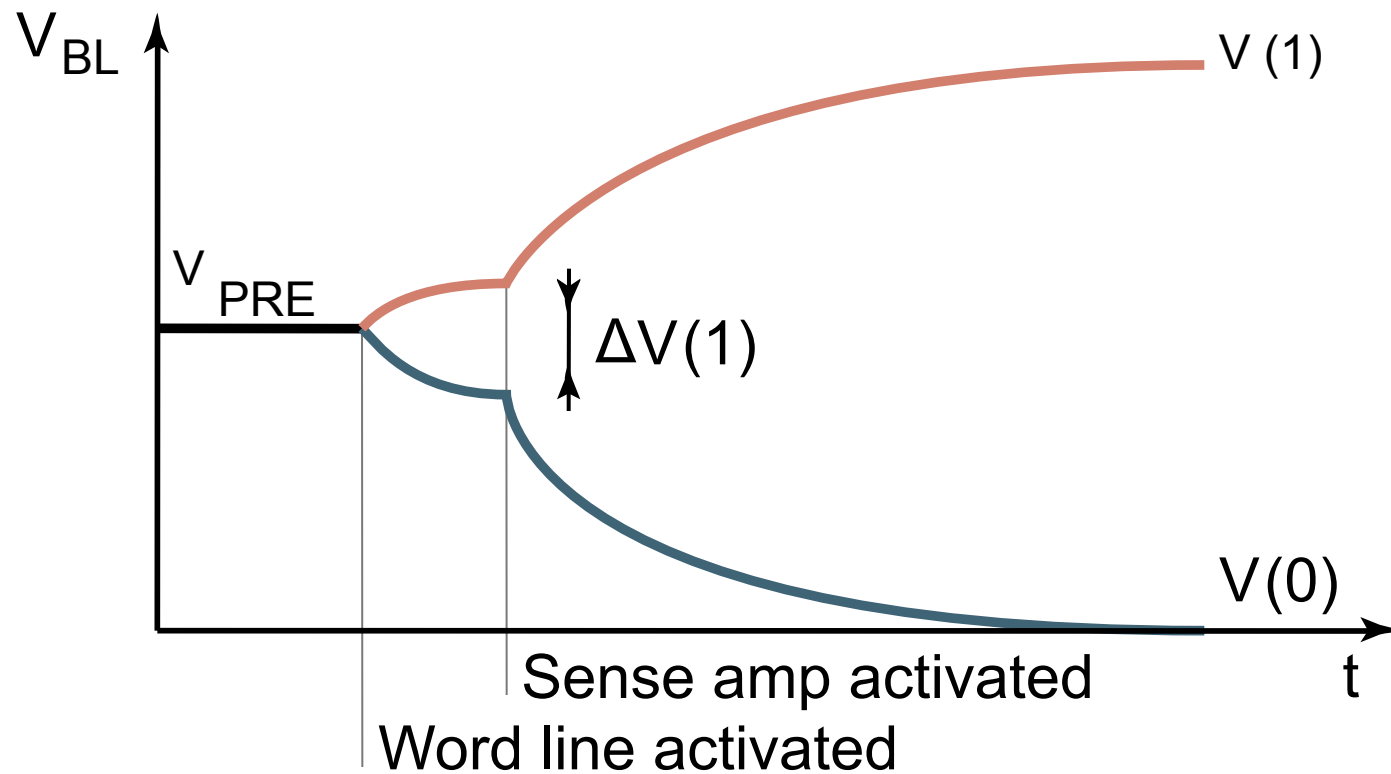
- Write: C_s is charged or discharged by asserting WL and BL
- Read: Charge redistribution takes place between bit line and storage capacitance
- Voltage swing is small; typically around 250 mV



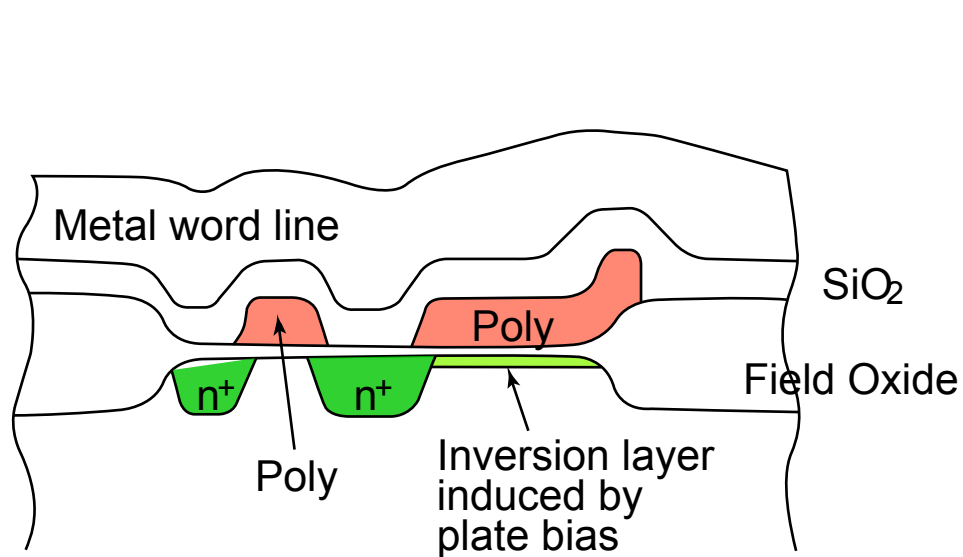
DRAM Cell Observations

- ❑ 1T DRAM requires a sense amplifier for each bit line, due to charge redistribution read-out.
- ❑ DRAM memory cells are single ended in contrast to SRAM cells.
- ❑ The read-out of the 1T DRAM cell is destructive; read and refresh operations are necessary for correct operation.
- ❑ Unlike 3T cell, 1T cell requires presence of an extra capacitance that must be explicitly included in the design.
- ❑ When writing a “1” into a DRAM cell, a threshold voltage is lost. This charge loss can be circumvented by bootstrapping the word lines to a higher value than V_{DD}

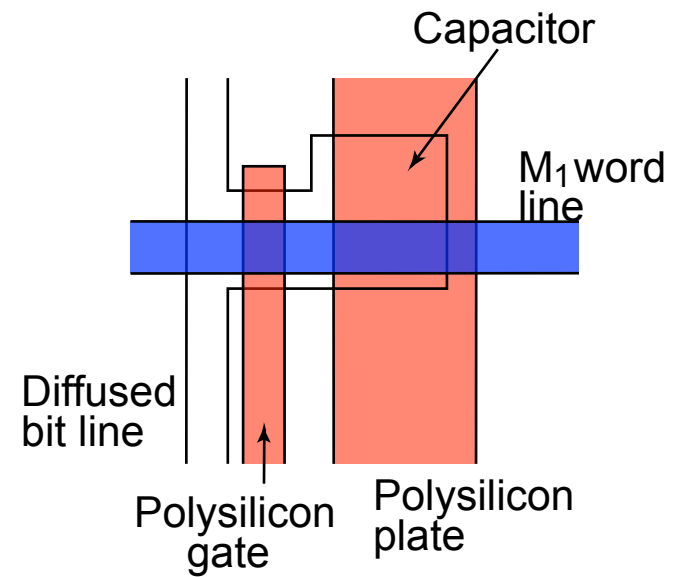
Sense Amp Operation



1-T DRAM Cell



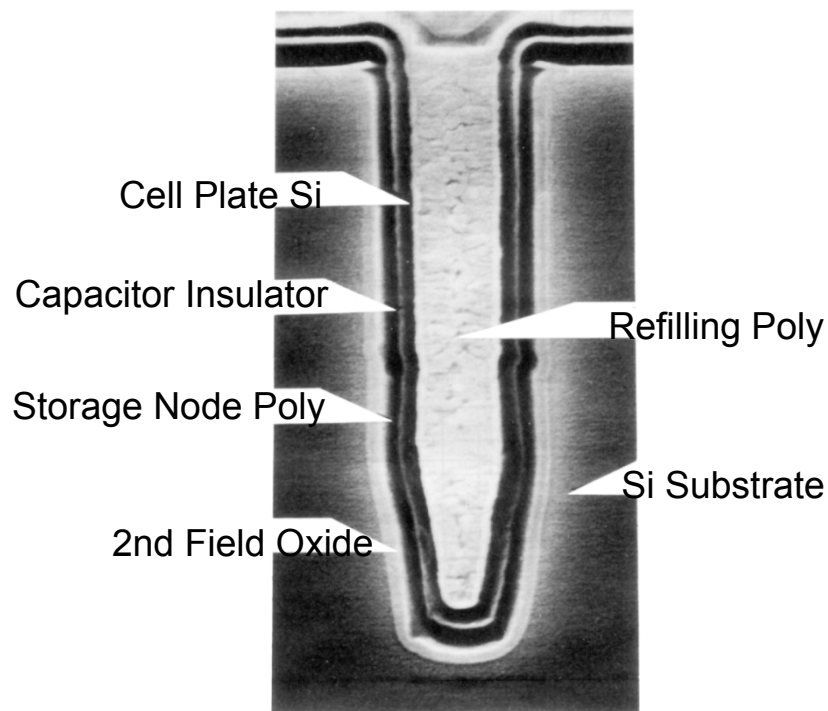
Cross-section



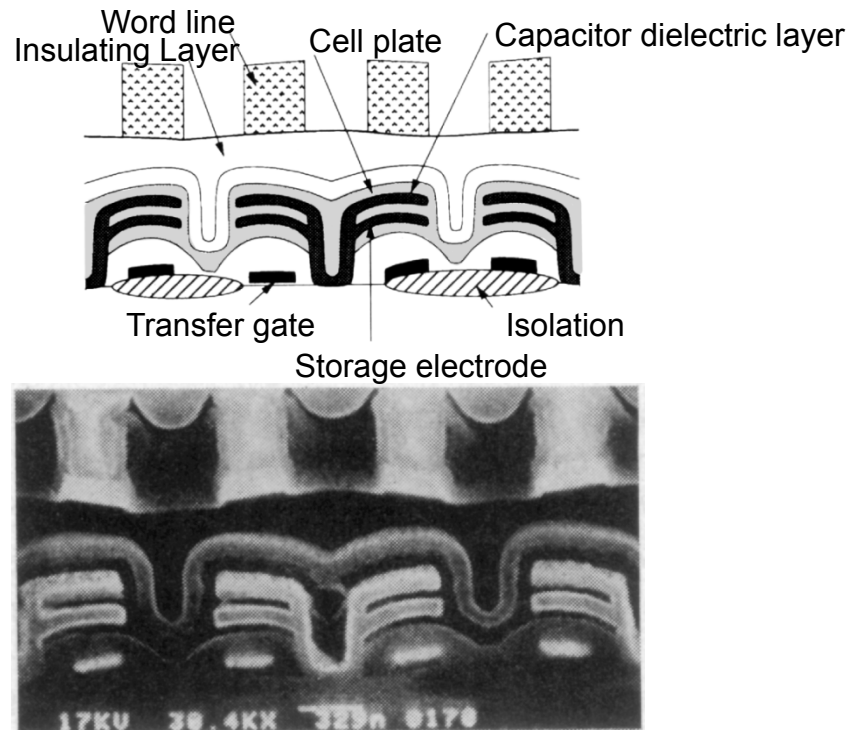
Layout

Uses Polysilicon-Diffusion Capacitance
Expensive in Area

Advanced 1T DRAM Cells

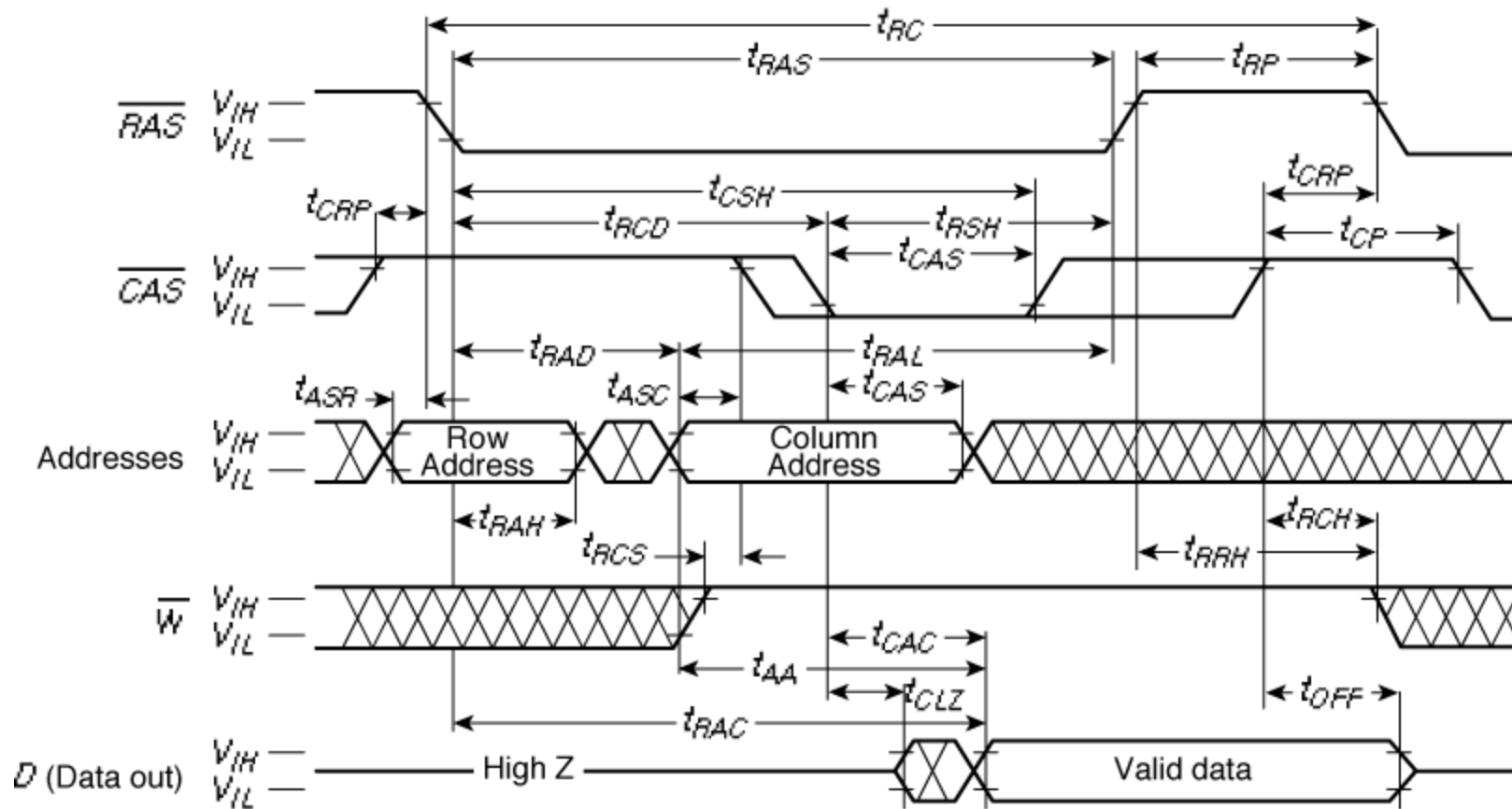


Trench Cell



Stacked-capacitor Cell

DRAM Timing



Redundancy

